

Designing Metal and Semiconductor Contact Heterostructures to Two-Dimensional MoSi_2N_4 and WSi_2N_4

Yee Sin Ang

Qianqian Wang, Che Chen Tho and L. K. Ang

Singapore University of Technology and Design, 8 Somapah Road, Singapore 487372

yeesin_ang@sutd.edu.sg

The recent discovery of two-dimensional (2D) MA_2Z_4 monolayers unravels an exciting material platform for a plethora of device applications [1]. Here we study the heterostructures of MA_2Z_4 using density functional theory (DFT) simulations [2-5]. Focusing on MoSi_2N_4 and WSi_2N_4 , we investigated three major classes of contacts: (i) 3D metals [2]; (ii) 2D metals [3]; and (3) 2D semiconductors [4,5]. For 3D metal contacts, we found that MoSi_2N_4 and WSi_2N_4 exhibit strongly suppressed Fermi level pinning effect [Figure 1 (a)]. Intriguingly, the presence of an outer Si-N layer offers a *built-in* protective mechanism that preserves the transport states situating in the inner core layer, thus significantly suppressing interfacial tunnelling barrier and avoiding severe metallization of the VBM and CBM states. For 2D metal contacts, nearly Ohmic and electric-field tunable contacts can be obtained using graphene and NbS_2 [3]. We further perform a comprehensive cataloguing of 2D/2D van der Waals heterostructures (vdWHs) between MA_2Z_4 and other 2D semiconductors [4,5]. By simulating 52 different types of MA_2Z_4 vdWHs, several candidate structures with excellent solar cell conversion efficiency reaching well over 20% are identified. Furthermore, we found that MoSi_2N_4 -and WSi_2N_4 -based vdWHs typically exhibit strong optical absorption in the ultraviolet (UV) regime, suggesting their potential for UV photonics applications [Figure 1 (b)]. Our findings uncover the contact properties of MoSi_2N_4 and WSi_2N_4 and reveal the opportunities of MA_2Z_4 as an emerging 2D material family towards the realization of novel solid-state technology beyond the silicon era.

References

- [1] Y.-L. Hong et al, Science, **369** (2020) 670
- [2] Q. Wang et al, NPJ 2D Mater. Appl., **5** (2021) 71
- [3] L. Cao, G. Zhou, Q. Wang, L. K. Ang, Y. S. Ang, Appl. Phys. Lett., **118** (2021) 013106
- [4] J. Q. Ng, Q. Wu, L. K. Ang and Y. S. Ang, Appl. Phys. Lett., **120** (2022) 103101
- [5] C. C. Tho, Y. S. Ang, et al, manuscript in preparation (2022)

Figures

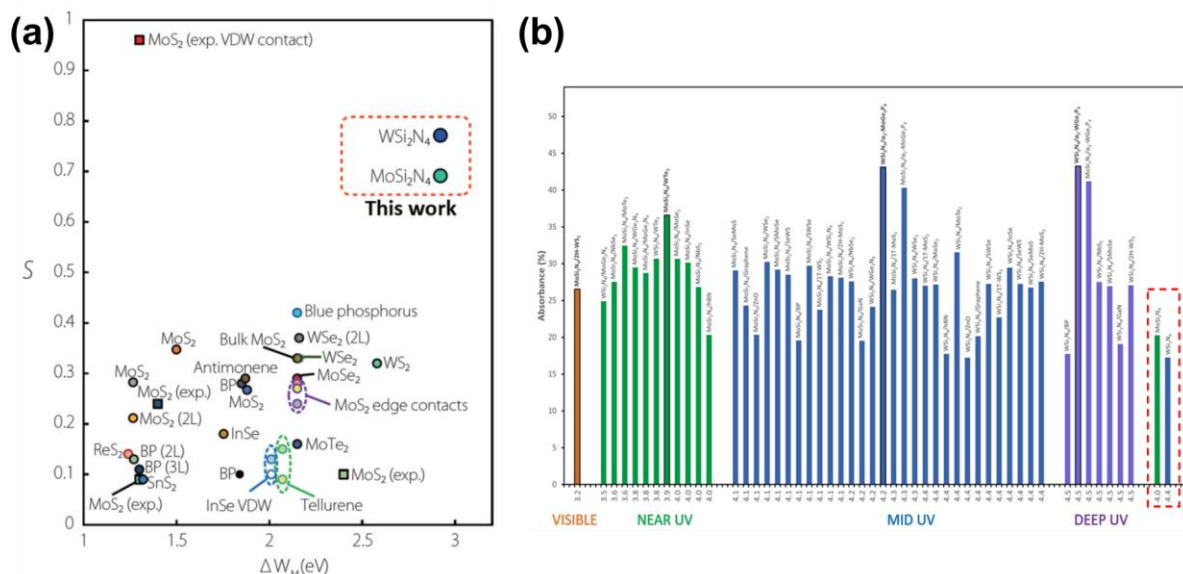


Figure 1: (a) Strongly suppressed FLP effect in MoSi_2N_4 and WSi_2N_4 metal contacts [2]. (b) 2D/2D VDWs based on MoSi_2N_4 and WSi_2N_4 exhibit strong optical absorption in the UV regime [5].